

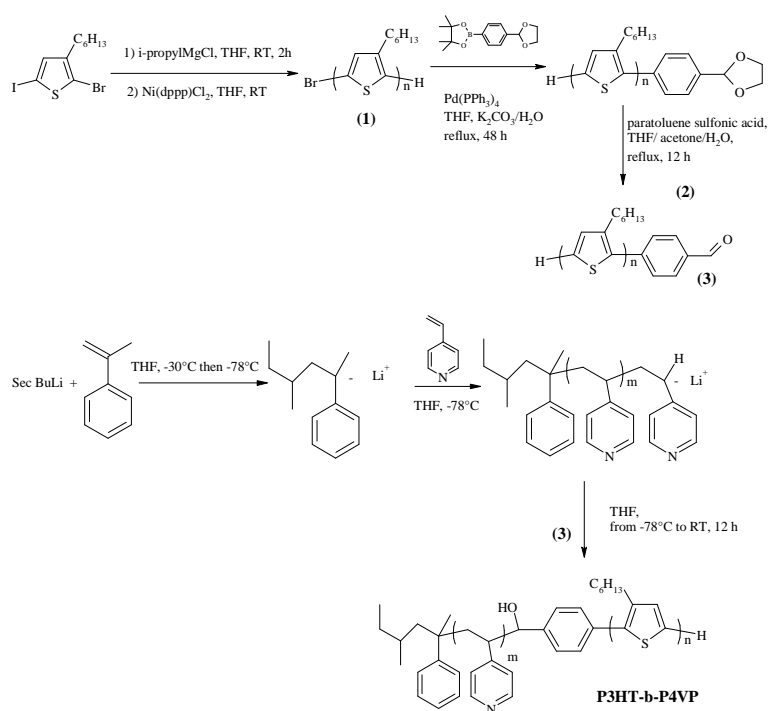
## Supporting Information

### A New Supramolecular Route for Using Rod-Coil Block Copolymers in Photovoltaic Applications

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#### Copolymer synthesis

The P3HT-P4VP block copolymer has been obtained by anionic polymerization of 4-vinylpyridine and quenching with an aldehyde end-functionalized P3HT (**3**) as summarized in Scheme S1. This route has been adapted from the synthesis of a poly(phenylene vinylene) (PPV)-based block copolymer previously described<sup>[S1]</sup> and will be discussed in more details in a separate manuscript focused on the block copolymer synthesis and characterisation.



**Scheme S1:** Schematic representation of block copolymer synthesis

The first P3HT block (**1**) was obtained by GRIM polymerization<sup>[S2]</sup>, and further functionalized by coupling on the bromine chain end, using a well known approach<sup>[S3]</sup> in order to obtain the P3HT (**2**). Aldehyde end-functionalized P3HT (**3**) was then obtained by deprotection reaction in acid conditions. The degree of functionalization (80%) was estimated by gel permeation chromatography of a P3HT-b-PS block copolymer obtained by quenching an anionic polymerization of styrene with the aldehyde end-functionalized P3HT (**3**).

Block copolymer synthesis was done by the quenching of anionic polymerization of 4-vinylpyridine with an aldehyde end-functionalized P3HT (**3**). According to the previous published synthesis conditions <sup>[S1]</sup> a large excess of living anionic P4VP chains were used. After quenching, the P4VP homopolymer was removed by washing several times (at least 3 times) the organic phase with HCl/H<sub>2</sub>O (pH=4). Molecular weights were not determined by GPC (due to the poor solubility of P3HT-*b*-P4VP copolymer), but estimated by NMR. Results are summarized in Table S1.

**Table S1:** characteristics of P3HT-*b*-P4VP copolymer.

|                           | Mn (kg/mol) * | Mn « rod » (kg/mol) * | Mn « coil » (kg/mol) * |
|---------------------------|---------------|-----------------------|------------------------|
| <b>P3HT</b>               | 8.7           | 8.7                   | 0                      |
| <b>P3HT-<i>b</i>-P4VP</b> | 11.6          | 8.7                   | 2.9                    |

\* determined by <sup>1</sup>H NMR

#### NMR characterizations :

##### - P3HT (**1**):

<sup>1</sup>H RMN 400 MHz, acquisition during 16h (CDCl<sub>3</sub>) : δ (ppm) 0.91 (t, n\*3H, aliph. CH<sub>3</sub>); 1.33 (m, n\*6H, aliph. CH<sub>2</sub>); 1.69 (m, n\*2H, aliph. CH<sub>2</sub>); 2.6 et 2.8 (m, n\*2H, aliph. CH<sub>2</sub>); 6.98 (s, n\*1H arom. CH); (n : degree of polymerization).

<sup>13</sup>C RMN ( CDCl<sub>3</sub>): δ (ppm) 139.9; 133.7; 130.5; 128.6; 31.7; 30.5; 29.5; 29.25; 22.6; 14.1.

##### - P3HT (**2**) :

<sup>1</sup>H RMN 400 MHz, acquisition during 16h (CDCl<sub>3</sub>) : δ (ppm) 0.91 (t, n\*3H, aliph. CH<sub>3</sub>); 1.33 (m, n\*6H, aliph. CH<sub>2</sub>); 1.69 (m, n\*2H, aliph. CH<sub>2</sub>); 2.6 et 2.8 (m, n\*2H, aliph. CH<sub>2</sub>); 4.1 (m, 4H, OCH<sub>2</sub> chain end); 5.87 (s, 1H CH chain end); 6.98 (s, n\*1H arom. CH); 7.50 (d, 2H arom. CH of chain end); 7.53 (d, 2H arom. CH of chain end); (with n being the degree of polymerization).

##### - P3HT (**3**) :

<sup>1</sup>H RMN 400 MHz, acquisition during 16h (CDCl<sub>3</sub>) : δ (ppm) 0.91 (t, n\*3H, aliph. CH<sub>3</sub>); 1,33 (m, n\*6H, aliph. CH<sub>2</sub>); 1.69 (m, n\*2H, aliph. CH<sub>2</sub>); 2.6 et 2.8 (m, n\*2H, aliph. CH<sub>2</sub>); 6.98 (s, n\*1H arom. CH); 7.64 (d, 2H arom. CH chain end); 7.93 (d, 2H arom. CH chain end); 10.05 (s, 1H aldehyde OCH).

- P3HT-b-P4VP block copolymer:

$^1\text{H}$  RMN 400 MHz, acquisition during 16h ( $\text{CDCl}_3$ ) :  $\delta$  (ppm) 0.91 (t,  $n*3\text{H}$ , aliph.  $\text{CH}_3$ , P3HT); 1.33 (m,  $n*6\text{H}$ , aliph.  $\text{CH}_2$ , P3HT); 1.69 (m,  $n*2\text{H}$ , aliph.  $\text{CH}_2$ , P3HT); 2.6 and 2.8 (m,  $n*2\text{H}$ , aliph.  $\text{CH}_2$ , P3HT); 6.28-6.4 (m,  $x*2\text{H}$  arom. CH, 4-VP); 6.98 (s,  $n*1\text{H}$  arom. CH, P3HT); 8.25-8.4 (m,  $m*2\text{H}$  arom. CH, 4-VP); (with  $n$  being the degree of polymerization of P3HT block and  $m$  the degree de polymerization of P4VP).

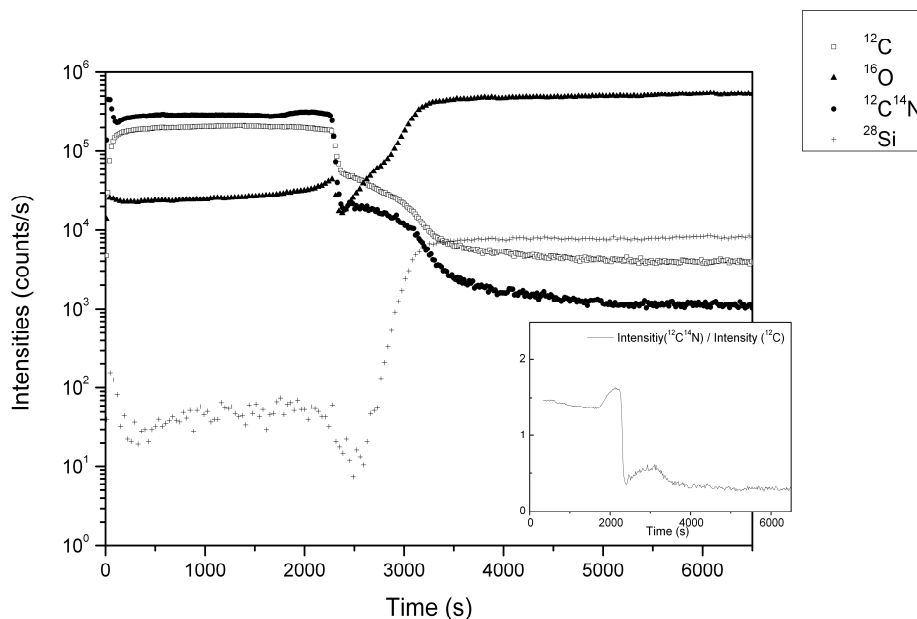
### Dynamic Secondary Ion Mass Spectrometry (D-SIMS)

The active layers used for photovoltaic purposes were characterized by Dynamic Secondary Ion Mass Spectrometry (D-SIMS) with low energy impact. The experiments reported here were carried out in ultra-high vacuum (UHV) using a  $\text{Cs}^+$  primary ion source at impact energy of 500 eV with negative ion detection to optimize the secondary detection. The  $^{12}\text{C}$  SIMS signal was used to identify the polymer layer while the  $^{12}\text{C}^{14}\text{N}$  SIMS signal was chosen to probe P4VP.

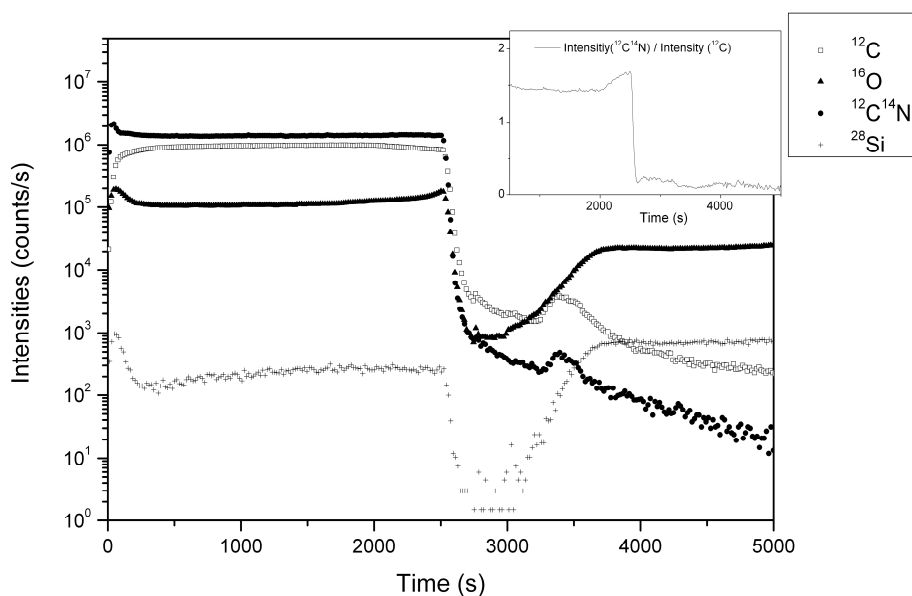
The  $^{12}\text{C}^{14}\text{N}$  signal is normalized by the matrix signal ( $^{12}\text{C}$ ) to follow the evolution of the concentration of nitrogen in the different layers.

SIMS depth profiles obtained on a P3HT-P4VP:PCBM/PEDOT:PSS layers, deposited on an oxidized silicon wafer, probing  $^{28}\text{Si}$  (crosses),  $^{12}\text{C}$  (open squares),  $^{16}\text{O}$  (close triangles) and  $^{12}\text{C}^{14}\text{N}$  (close circles) are shown in Figure S1 and S3 for C8 and C17, respectively. *Insert* :  $^{12}\text{C}^{14}\text{N}$  signal normalized by the  $^{12}\text{C}$  signal (polymer matrix), to attenuate a possible matrix effect.

Both interfaces with the PEDOT:PSS layer can be clearly identified : the PEDOT:PSS / $\text{SiO}_2$  interface is marked by the rapidly increasing  $^{28}\text{Si}$  signal, while the P3HT-P4VP:PCBM/PEDOT:PSS interface is shown by the drop in the  $^{12}\text{C}$  signal. Importantly, the significant increase of the  $^{12}\text{C}^{14}\text{N}/^{12}\text{C}$  signal ratio close to the PEDOT:PSS layer can be attributed to P4VP accumulation at the interface. A similar peak in the distribution of  $^{16}\text{O}$  can also be observed and could be explained by a local increase in PCBM concentration.



**Figure S1:** SIMS depth profiles obtained on a P3HT-P4VP:PCBM/PEDOT:PSS active layer with 8 % of PCBM (equivalent to C8), deposited on an oxidized silicon wafer, probing  $^{28}\text{Si}$  (crosses),  $^{12}\text{C}$  (squares),  $^{16}\text{O}$  (triangles) and  $^{12}\text{C}^{14}\text{N}$  (circles). *Insert* :  $^{12}\text{C}^{14}\text{N}$  signal normalized by the  $^{12}\text{C}$  signal (polymer matrix), to attenuate a possible matrix effect.



**Figure S2:** SIMS depth profiles obtained on a P3HT-P4VP:PCBM/PEDOT:PSS active layer with 17 % of PCBM (equivalent to C17), deposited on an oxidized silicon wafer, probing  $^{28}\text{Si}$  (crosses),  $^{12}\text{C}$  (squares),  $^{16}\text{O}$  (triangles) and  $^{12}\text{C}^{14}\text{N}$  (circles). *Insert* :  $^{12}\text{C}^{14}\text{N}$  signal normalized by the  $^{12}\text{C}$  signal (polymer matrix), to attenuate a possible matrix effect.

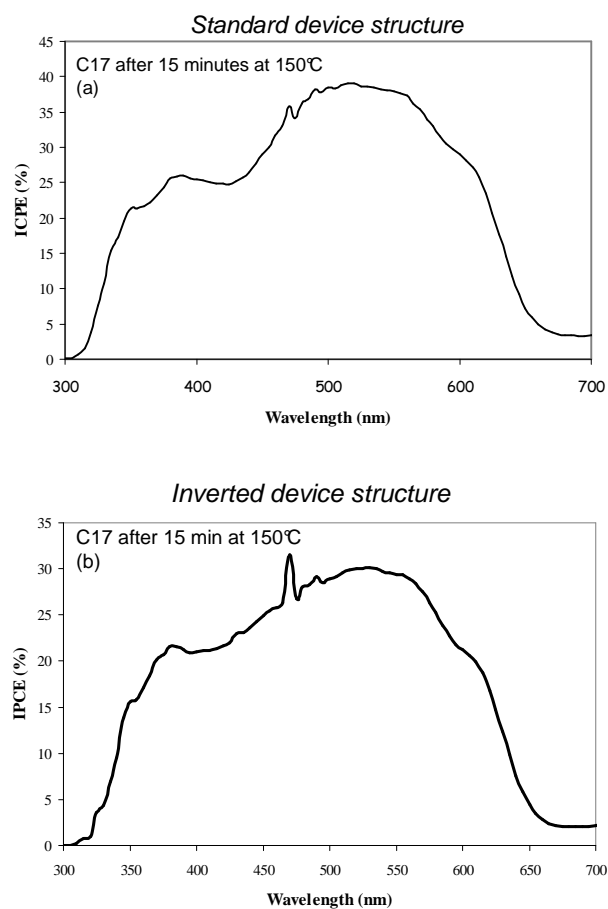
### Standard device performances

Table S2 reports blend compositions and major photovoltaic parameters for devices using various P3HT-P4VP/PCBM blends.

**Table S2**

|                                | C8     | C17    | C36    |
|--------------------------------|--------|--------|--------|
| % vol PCBM (overall)           | 8      | 17     | 36     |
| % vol PCBM (vs 4VP)            | 31     | 78     | 216    |
| % vol PCBM (vs P3HT)           | 11     | 28     | 76     |
| $J_{SC}$ (mA/cm <sup>2</sup> ) | 0.21   | 0.43   | 0.71   |
| $V_{OC}$ (V)                   | 0.33   | 0.29   | 0.29   |
| FF                             | 30%    | 21%    | 14%    |
| Energy Conversion Efficiency   | 0.017% | 0.026% | 0.026% |

## Incident-photon to current conversion efficiencies



**Figure S3.** Incident photon-to-current conversion efficiency (or IPCE) for the C17 active layer in a standard device structure (a) and inverted device structure (b). The peak at 480 nm is an artefact due to the mono-chromator (grating exchange)

## References

- [S1] N. Sary, L. Rubatat, C. Brochon, G. Hadziioannou, J. Ruokolainen, R. Mezzenga, *Macromolecules* **2007**, *40*, 6990.
- [S2] R. Miyakoshi, A. Yokoyama, T. Yokozawa, *J. Am. Chem. Soc.* **2005**, *127*, 17542
- [S3] J. Liu, R.D. McCullough *Macromolecules* **2002**, *35*, 9882.